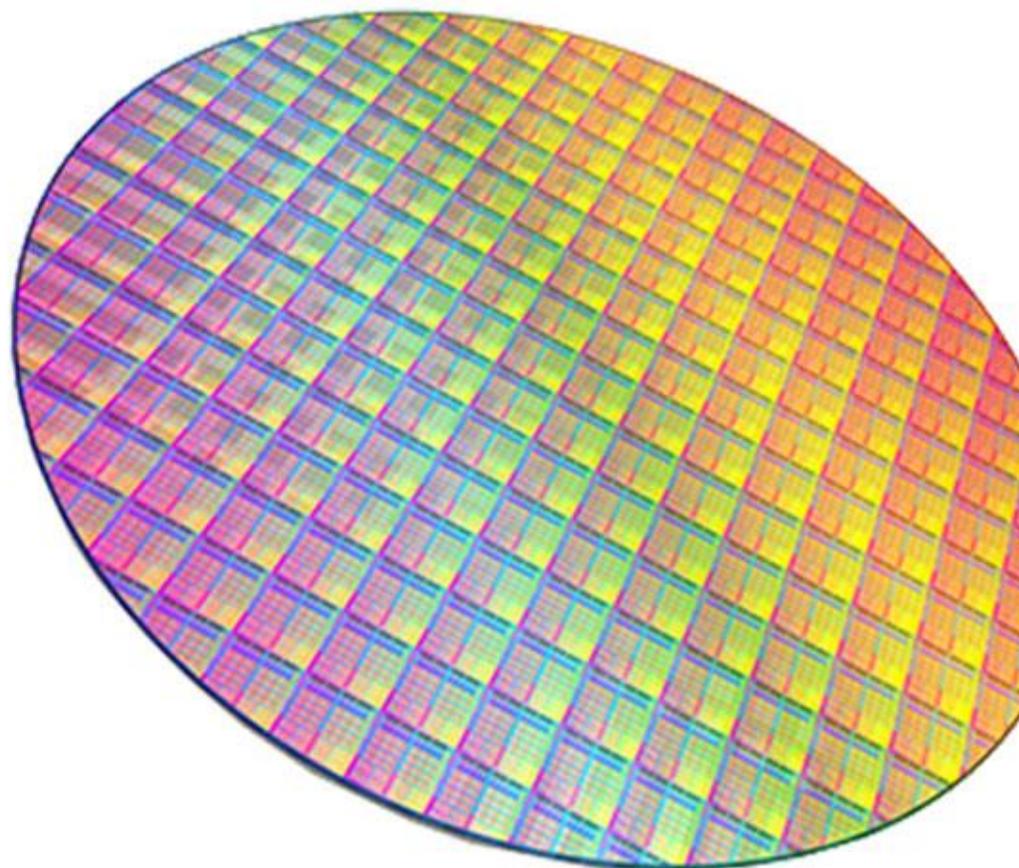




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# Physical Design & Signoff

FDP University Program 2023

Sanjay Kumar



arm  
Education



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# Let me introduce myself



- ❖ With 13+ years of experience in semiconductor industry.
- ❖ Graduated from NIT Calicut in Electronics and Communication Engineering.
- ❖ Currently managing the SoC Physical Design team for General Purpose Micro (GPM) products in ST, Greater Noida.
- ❖ Contributed to multiple successful tape-outs of products ranging from 180nm to 5nm technologies in consumer, automotive and industrial application.
- ❖ As part of SoC Physical Design, I have driven key initiatives in implementation of high-speed complex subsystems, and critical IPs for best-in-class power, performance, and area.
- ❖ In addition, have multiple publications / presentations and tech poster in various forums.

# Agenda

# ASIC Design Flow

# Physical Design Introduction

# Synthesis

# Floorplan (IO-Ring)

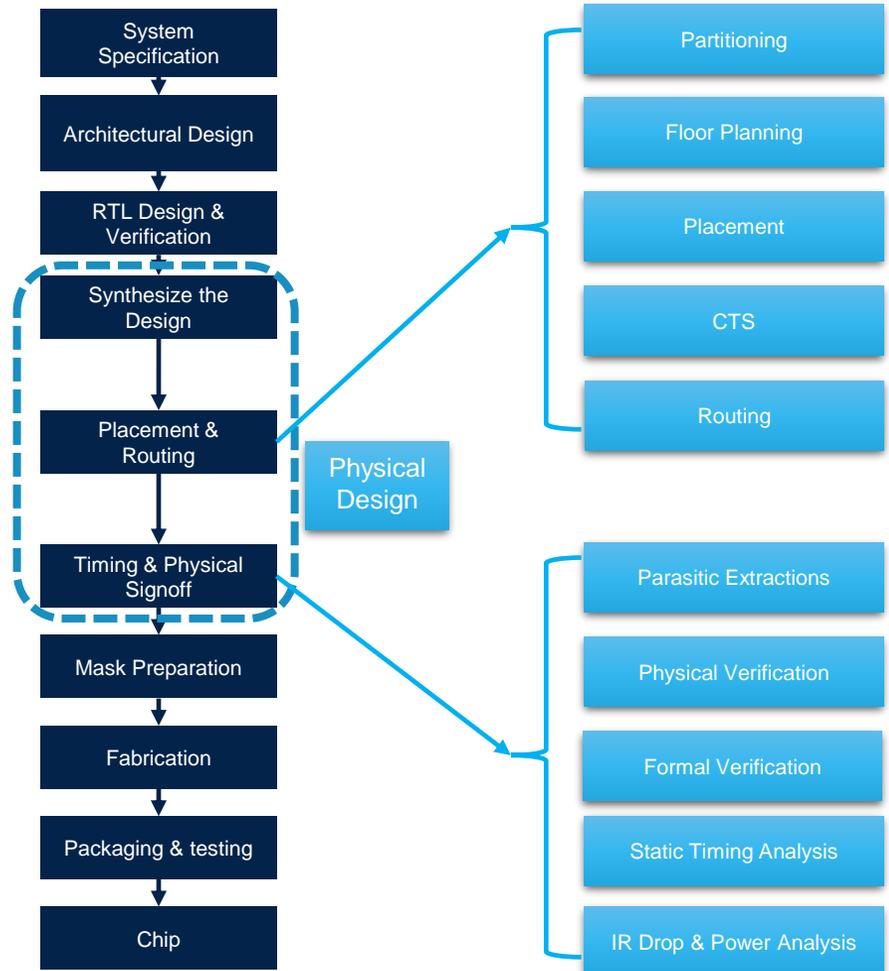
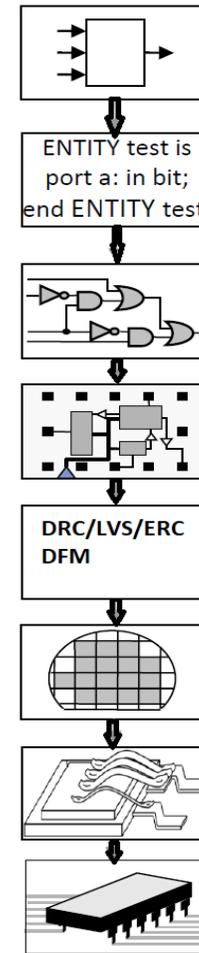
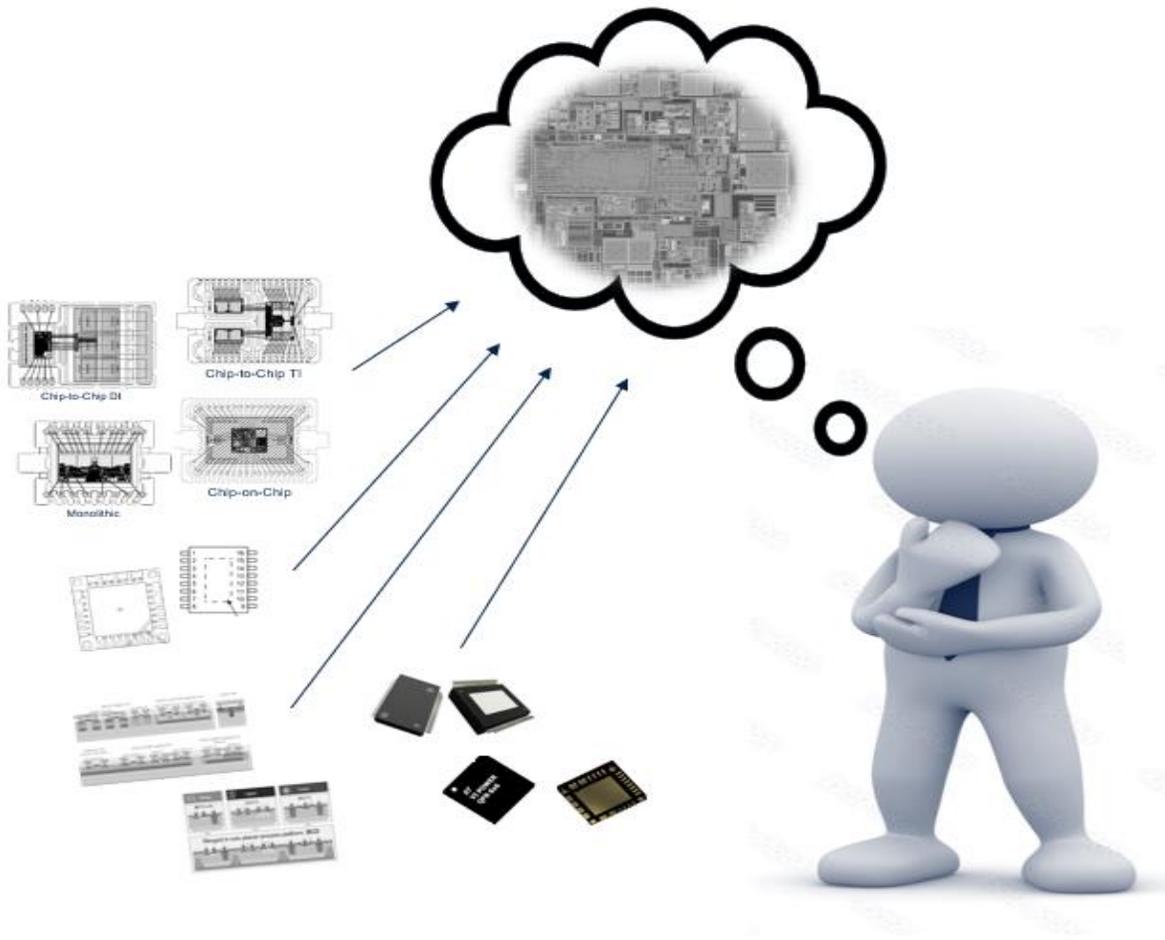
# Placement and Routing

# Physical Signoff

# Timing Signoff

# Power & IR Drop Analysis

# ASIC Design Flow

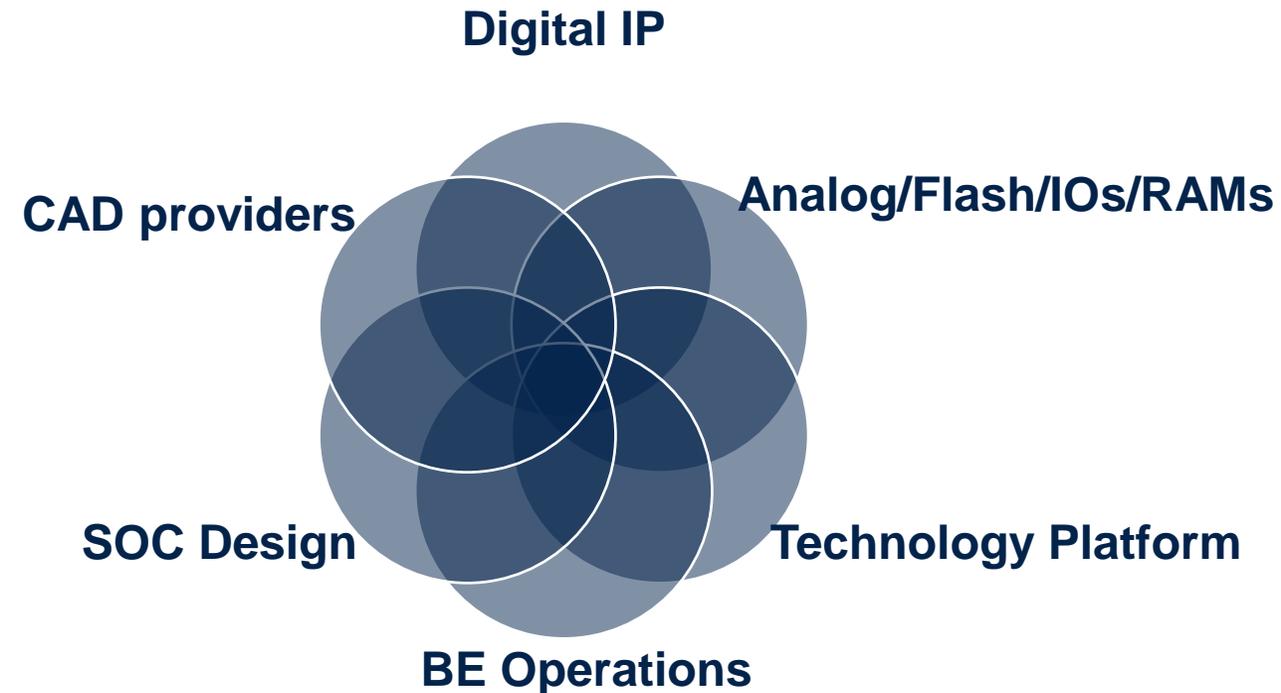


# Physical Design Team Mission

Physically implement most optimized system-on-chip designs while meeting project schedule, high level Power Performance Area targets/budgets and package constraints.

# Physical Design Team Engagements

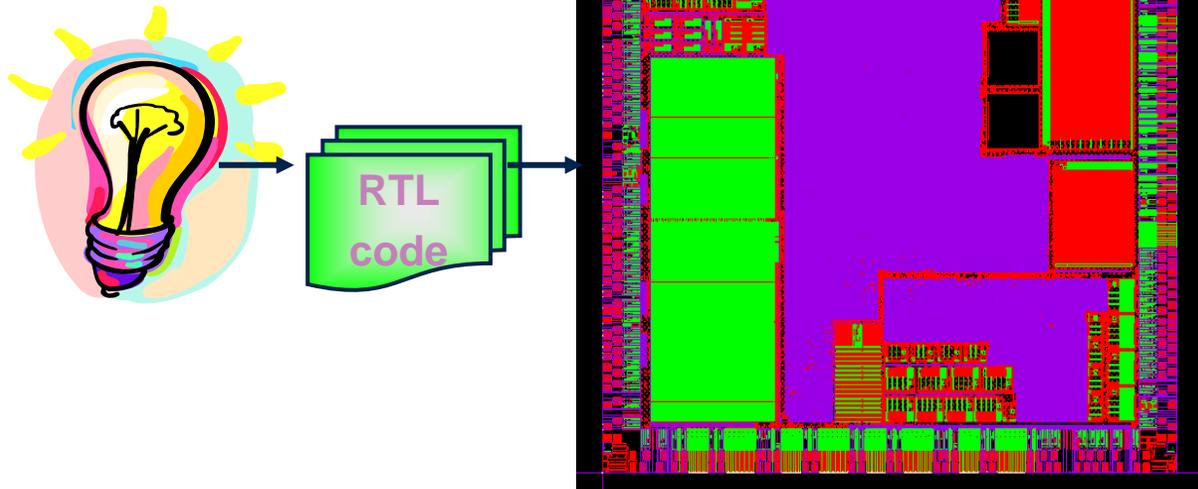
- Interface with...
  - SOC FE team to define PPA budgets
  - Technology providers (ST or external)
  - Package solution team
- Define & optimize implementation methodologies
- Define the right toolset to support these methodologies
- Define & deliver the SOC implementation schedule & resource plan
- Propose IP/SOC changes for better and most optimized SOC
- Top level planning/pad-ring construction/Analog integration
- Physical signoff checks
- Packaging assessment



# Physical Design flow - scope

## **Front End Design must guarantee:**

- Functionality
- Testability
- Reliability



## **Back End Design needs:**

- Chip architecture understanding
- Front end know how
- Technology information
- Implementation and Production steps know how
- Knowledge of testability requirements
- Backend CAD tools deep knowledge

# Physical Design Introduction

❑ Structural representation to Physical Design i.e., RTL to GDSII

❑ Stages:

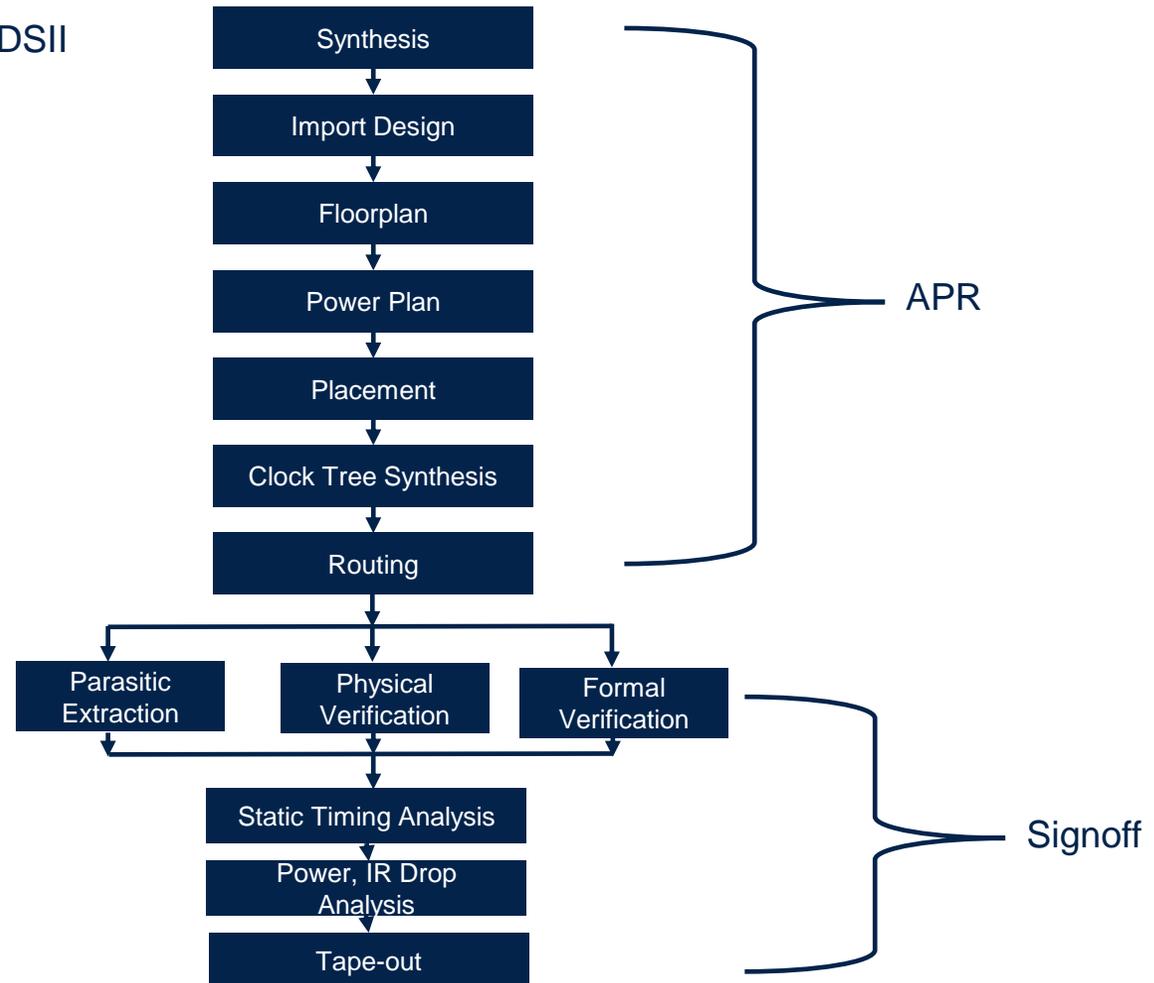
- ❑ Synthesis
- ❑ Placement and Routing (PnR)
- ❑ Signoff

❑ Objectives:

- ❑ Timing
- ❑ Congestion
- ❑ Area
- ❑ Power

❑ Possible Issues:

- ❑ Timing Violations
- ❑ Congestion Issues
- ❑ Design Rule Violations



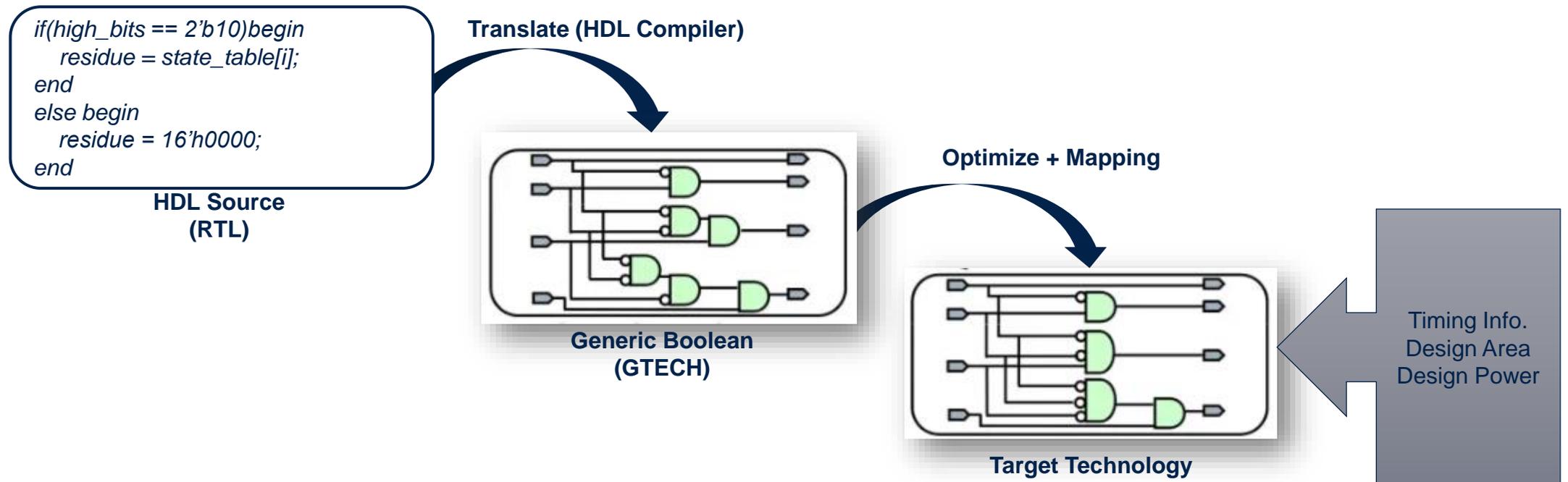
# Synthesis

```
if(typed  
return  
} else {  
let tan = this.tangent(u, v);  
let bitan = this.bitangent(u, v);  
if(MathInternal.vecLength(bitan) === 0) {  
return tan;  
}  
if(MathInternal.vecLength(tan) !== 0) {  
if(tan.length !== 3 || bitan.length !== 3) {  
let dims = tan.length;  
let ret = MathInternal.  
tan = [tan[0] || 0, tan[1] || 0, tan[2] || 0];  
bitan = [bitan[0] || 0, bitan[1] || 0, bitan[2] || 0];  
ret[0] = [0];  
ret[1] = [1];  
ret[2] = [2];  
slice(0, bitan.length);  
return bitan;  
}
```



# Synthesis (1/2)

- ❑ Process of transferring HDL to Gate-level netlist and described as
  - ❑ Synthesis = Translation + Logic Optimization + Mapping
- ❑ HDL => Generic Boolean Logic => Optimization => Mapping => Netlist



# Synthesis (2/2)

## ❑ Goal of Synthesis

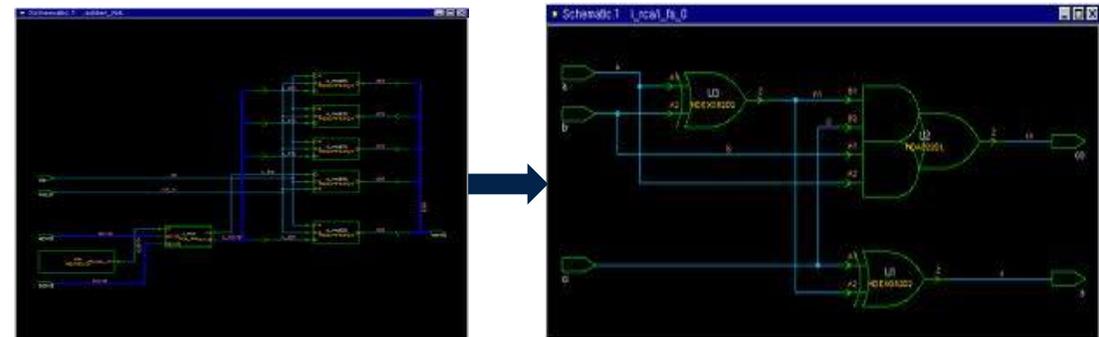
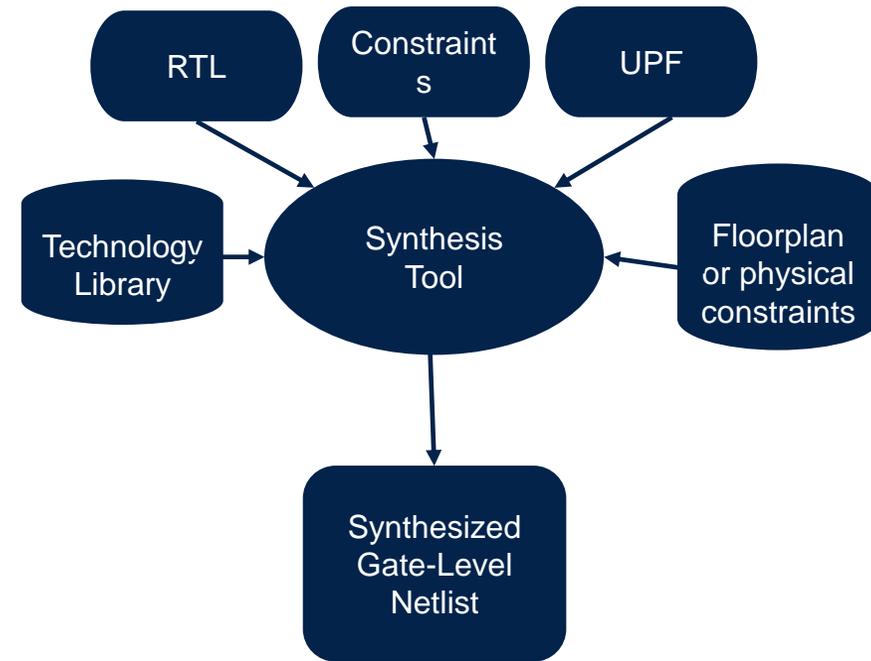
- ❑ To get a Gate-level Netlist
- ❑ Logic Optimization
- ❑ Inserting DFT Logic
- ❑ Logic Equivalence between RTL and Netlist should be maintained.

## ❑ Inputs of Synthesis

- ❑ RTL: HDL files
- ❑ Library views
- ❑ Constraints
- ❑ Floorplan DEF (for physical synthesis)
- ❑ UPF (Power intent for power aware synthesis)

## ❑ Outputs of Synthesis

- ❑ Netlist
- ❑ QoR Reports (timings, area, cell count etc.)
- ❑ UPF



# Library Views (1/2)

- ❑ LIBRARY: Consolidated Data for Use in Designing a System On Chip.

- ❑ Various Types of Libraries:

- ❑ CORE Libraries
- ❑ IO Libraries
- ❑ Memories
- ❑ Analog and Mixed Signal

- ❑ CORE Libraries:

- ❑ Group of basic logic functional cells, called std cells.
- ❑ Type of cells: AND, OR, Flops, Latch etc.
- ❑ Physical/logic/timing/electric models are present

- ❑ IO Libraries:

- ❑ IO buffers are designed for specific process technology.
- ❑ Power/Ground IOs for chip supply
- ❑ IOs are with protection of ESD events.

- ❑ Memories:

- ❑ Memories like SRAM, DRAM, ROM etc.
- ❑ Implemented as generator and configure various size of memory.
- ❑ Supports many features like redundancy, masking etc.

- ❑ Analog and Mixed Signal Libraries:

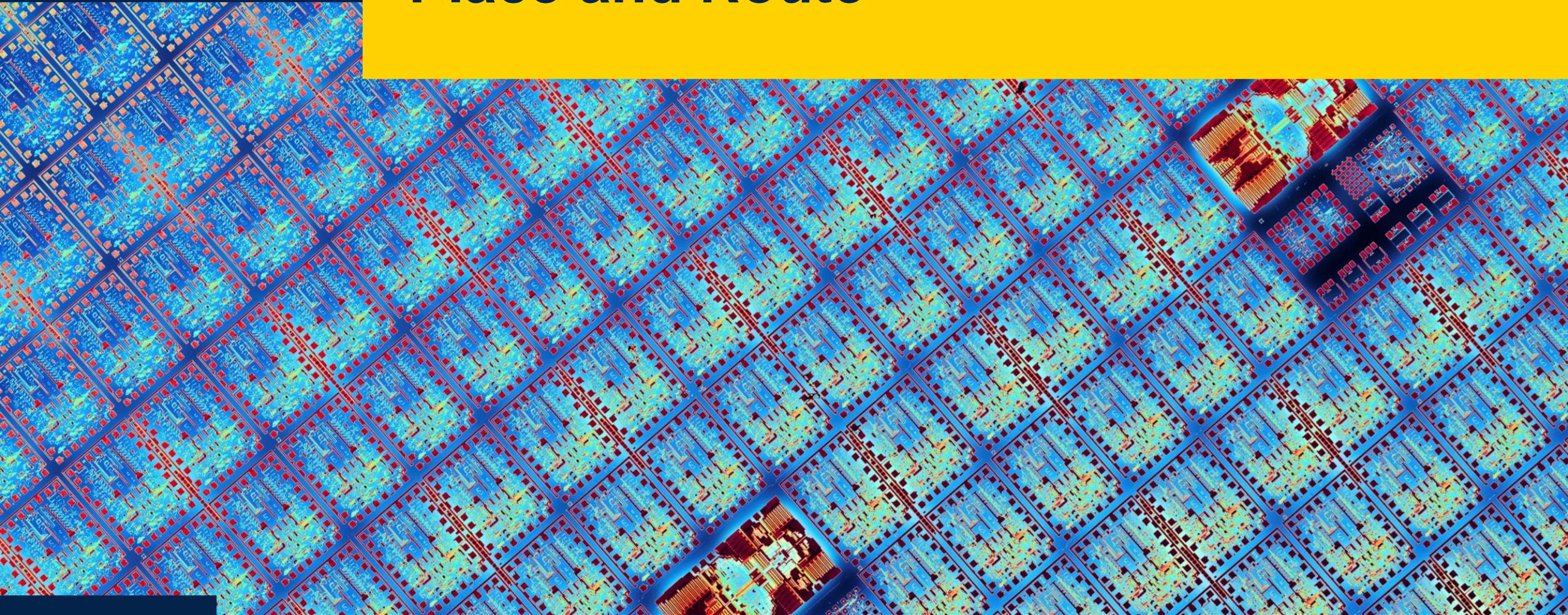
- ❑ These IPs provides unique functions
- ❑ Examples are PLL, ADC, DAC, USB, SATA etc

- ❑ Types of Views:

- ❑ HDL models
- ❑ Timing Libs
- ❑ Schematic
- ❑ Symbol
- ❑ Layout (LEF/GDSII)
- ❑ Abstract and more ...



# Place and Route



# PnR Inputs (1/2)

## Netlist/Verilog

- Std. cell instance name & drive strength
- Macros & memories instances
- Design module definitions
- Interconnection details

## Constraints

- Timing Constraints like Clock Definitions (clock period, duty cycle) and uncertainties.
- Timing Exceptions (False Paths, Asynchronous Paths).
- Delay Constraints (Latency, Input Delay, Input Transition, Output Load and Output Transition)
- Design rule constraints like Max. Cap / Transition / Fanout.

## Liberty Timing Files

- Cell Logical View / The timing Library
- Std Cell Lib, Macro Lib, IO lib
- Gate Delay

## Liberty Exchange Format (LEF)

- Cell Abstract View / The Physical Library
- Std Cell LEF
- Macro LEF
- IO LEF

## Technology File

- Defines Units, Design Rules for Layers and VIAS as per technology
- Physical and Electrical Parameters
- Metal direction/pitch/width/offset/thickness/resistance/capacitance etc.
- Site/Unit Tile definition

## Interconnect Parasitic File

- Used for layer parasitic extraction
- Contains layer/via cap and resistance values in lookup table

## Map file

- Useful if there is 2 different naming conventions in Technology file, LEF or Interconnect Parasitic file



# PnR Inputs (2/2)

## ❑ Power Specification File

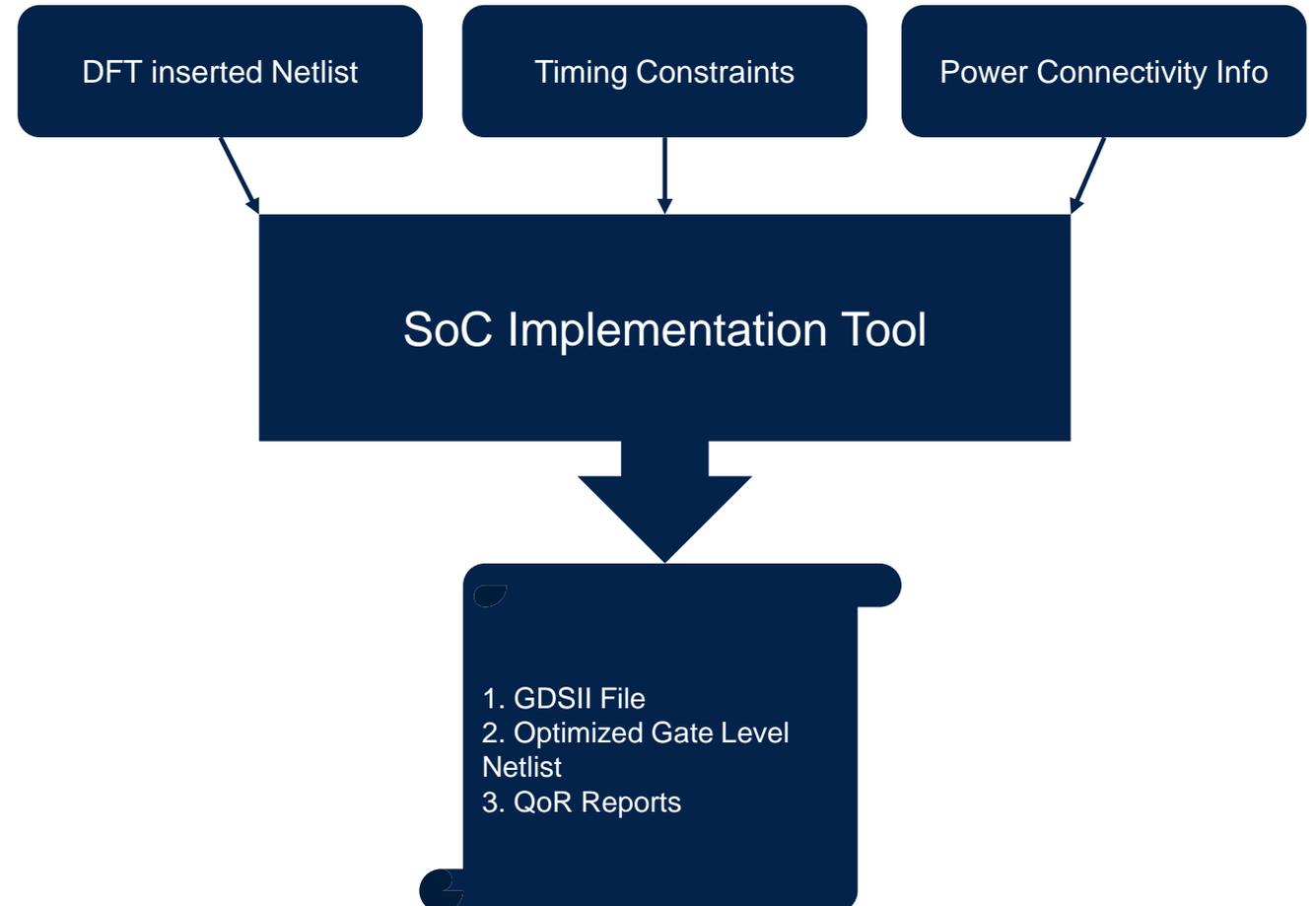
- ❑ Power Modes & Power Domains
- ❑ Tie Up supply & Tie Low supply
- ❑ Power Nets & GND Nets

## ❑ Optimization Directives

- ❑ Don't Use Cells
- ❑ Don't Touch
- ❑ Size only

## ❑ Clock Tree Constraints

- ❑ Root Pin Definition
- ❑ Insertion delay and skew targets
- ❑ Max Cap/Tran limits (DRVs)
- ❑ List of Buffers/Inverters for CTS
- ❑ NDRs for Clock Routes
- ❑ Macro Models if applicable.



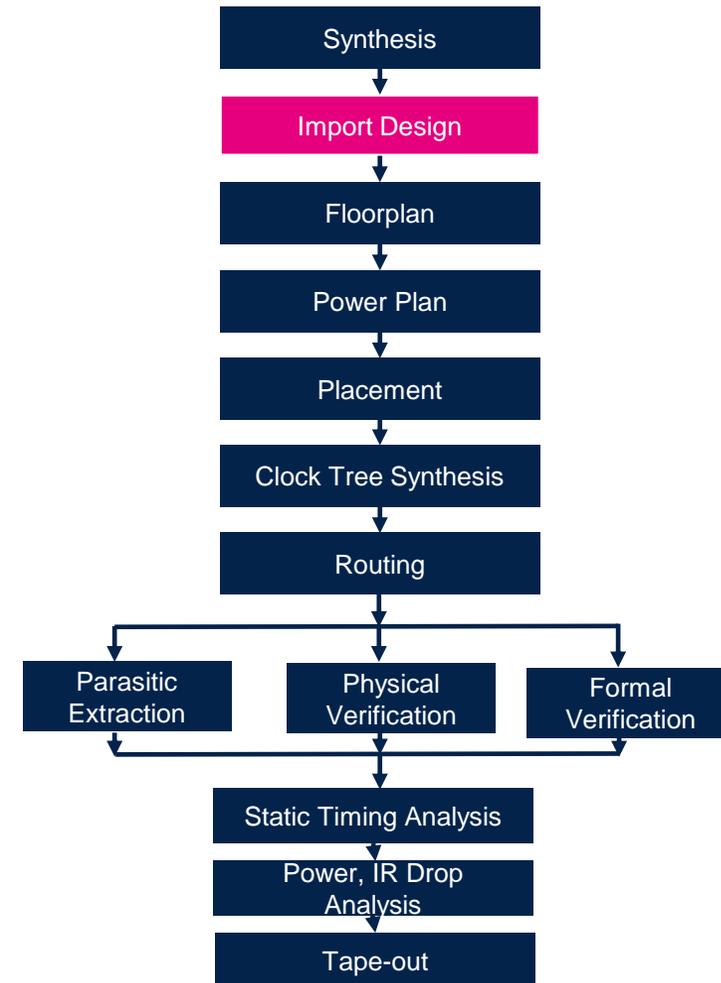
# Import Design

## ❑ The following input files information are loaded to the PnR tool

- ❑ Netlist (.v/ .vhd/ .edif)
- ❑ Physical Libraries (.lef)
- ❑ Timing Libraries (.lib)
- ❑ Technology Files
- ❑ Constraints (.sdc)
- ❑ IO Info. File (optional)
- ❑ Power Spec. File (optional)
- ❑ Optimization Directives (optional)
- ❑ Clock Tree Spec. File (optional at floorplan stage)
- ❑ DEF/ FP (optional if floorplan is not done)

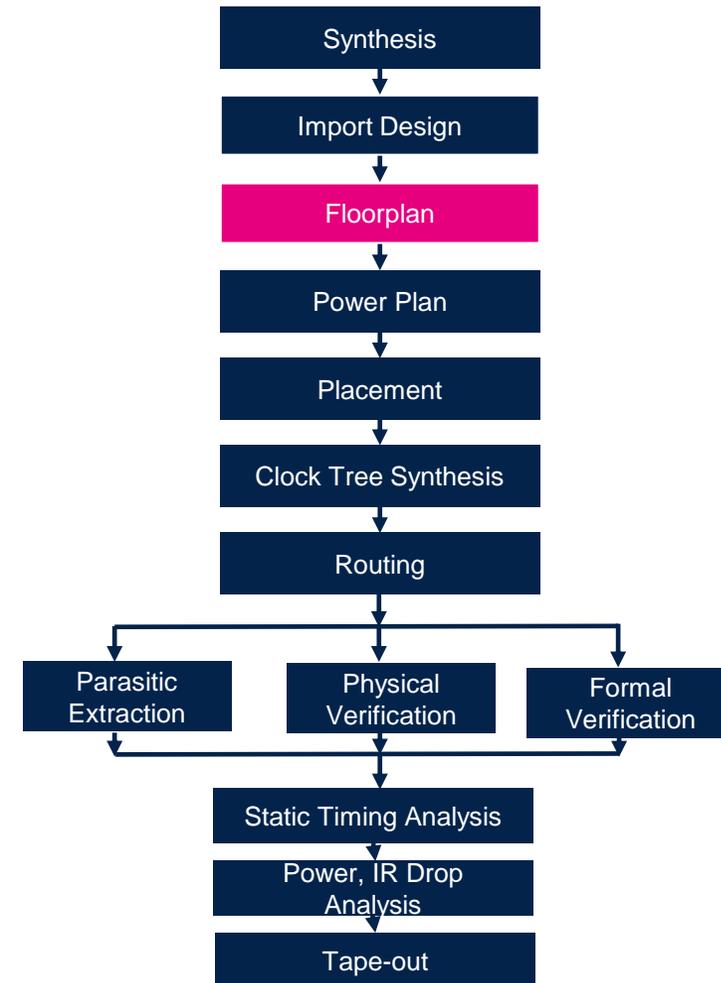
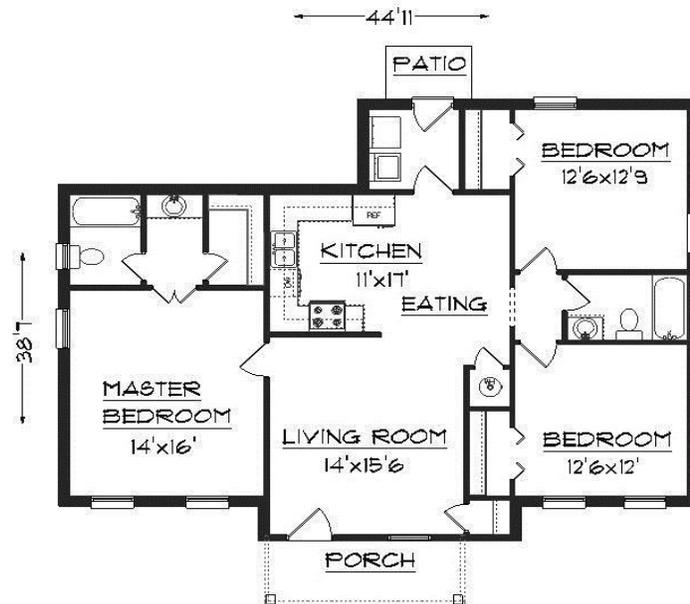
## ❑ Sanity Checks

- ❑ Sanity Checks mainly checks the quality of netlist in terms of timing
- ❑ It also consists of checking the issues related to Library files, Timing Constraints, IOs and Optimization Directives.
- ❑ Netlist Sanity Checks like floating pins, un-driven i/p ports, unloaded o/p ports multiple drivers etc.



# Floorplan

- ❑ To achieve best PPA
- ❑ To minimize issues like placement density, congestion, timing challenges
- ❑ To Reduce wire length and making routing easy.
- ❑ To reduce Si cost



# Floorplan

## ❑ Important Terminologies in Floorplan

- ❑ Utilization
- ❑ Manufacturing Grid
- ❑ Std Cells Site / Placement Tile / Unit Tile
- ❑ Std Cell Rows
- ❑ Placement Grid
- ❑ Routing Grid and Routing Track
- ❑ Flight-Line / Fly-Line
- ❑ Macros

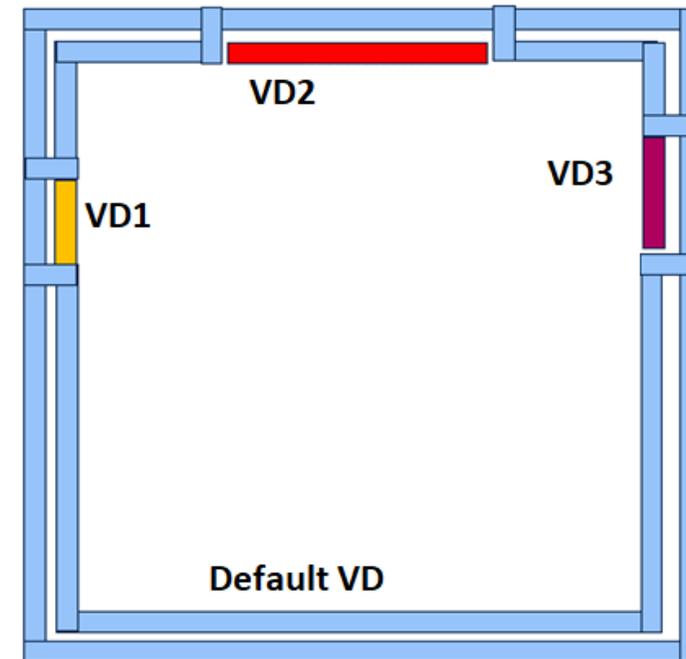
## ❑ Steps in Floorplan

- ❑ Initialize fp with Chip & Core Aspect Ratio (AR) and with Core Utilization
- ❑ Initialize fp Row Configuration & Cell Orientation
- ❑ Provide the Core to Pad/ IO spacing (Core to IO clearance)
- ❑ Pins/ Pads Placement
- ❑ Macro Placement by Fly-line Analysis
- ❑ Blockage Management (Placement/ Routing)



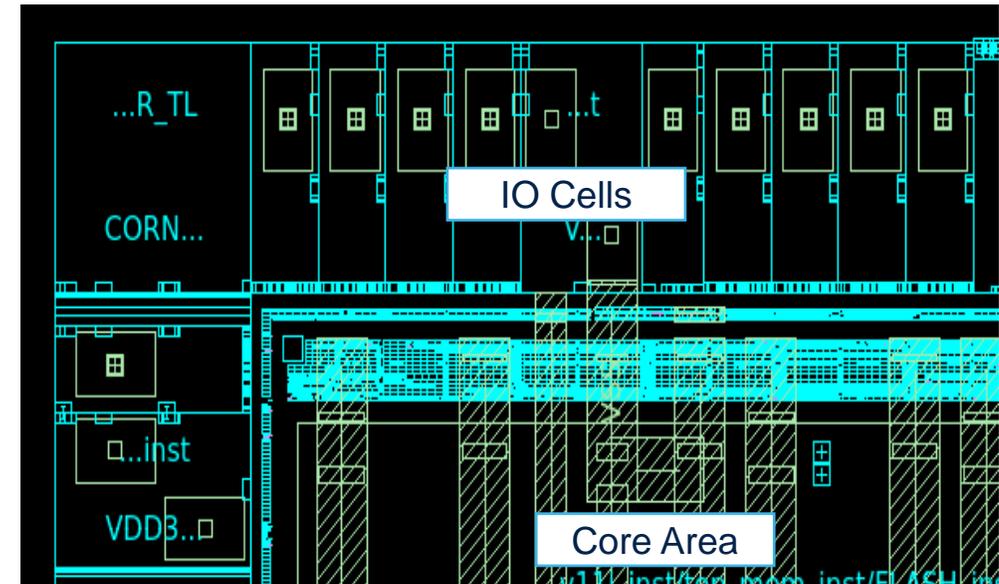
# IO-Ring Introduction

- ❑ Interface between the package and the chip
- ❑ Type of IOs
  - ❑ IO and core Power Pads
  - ❑ Signal Pads
  - ❑ Corner PADS
  - ❑ Protection from outside aggression (ESD)
- ❑ IOs are abutted to create PAD Ring
- ❑ Multi Voltage Design support
- ❑ Multi Package Compatibility



## ❑ IO Placement

- ❑ Chip Level => IO Pads and Block Level => IO Pins
- ❑ Pin is a logical entity and is a property of a Port and Port is a physical entity and only 1 Pin associated with it.
- ❑ Netlist will have Pins and Layout will have Ports
- ❑ Different types of IO PADs
  - ❑ Signal Pads/Pins
  - ❑ Core Power Pads/Pins
  - ❑ IO Power Pads/Pins
  - ❑ Corner Pads
  - ❑ Filler Pads (Fill the gaps between IO pads to get the Ring Connectivity)
- ❑ Physical-only pads that are not part of the input Gate level Netlist need to be inserted prior to reading IO constraints.
- ❑ IO Pads enables the design to operate at different voltages with the help of Level Shifters, Pre-Drivers (at Core Voltage) Post-Drivers (at IO Voltage)



# Power Plan

- ❑ To connect power to the chip by considering issues like EM and IR Drop

- ❑ Levels of Power Distribution

- ❑ Rings :  $V_{DD}$  &  $V_{SS}$  Rings are created around the core and Macro
- ❑ Stripes:  $V_{DD}$  &  $V_{SS}$  Power Stripes are created in the core area

- ❑ Special Route (Rails)

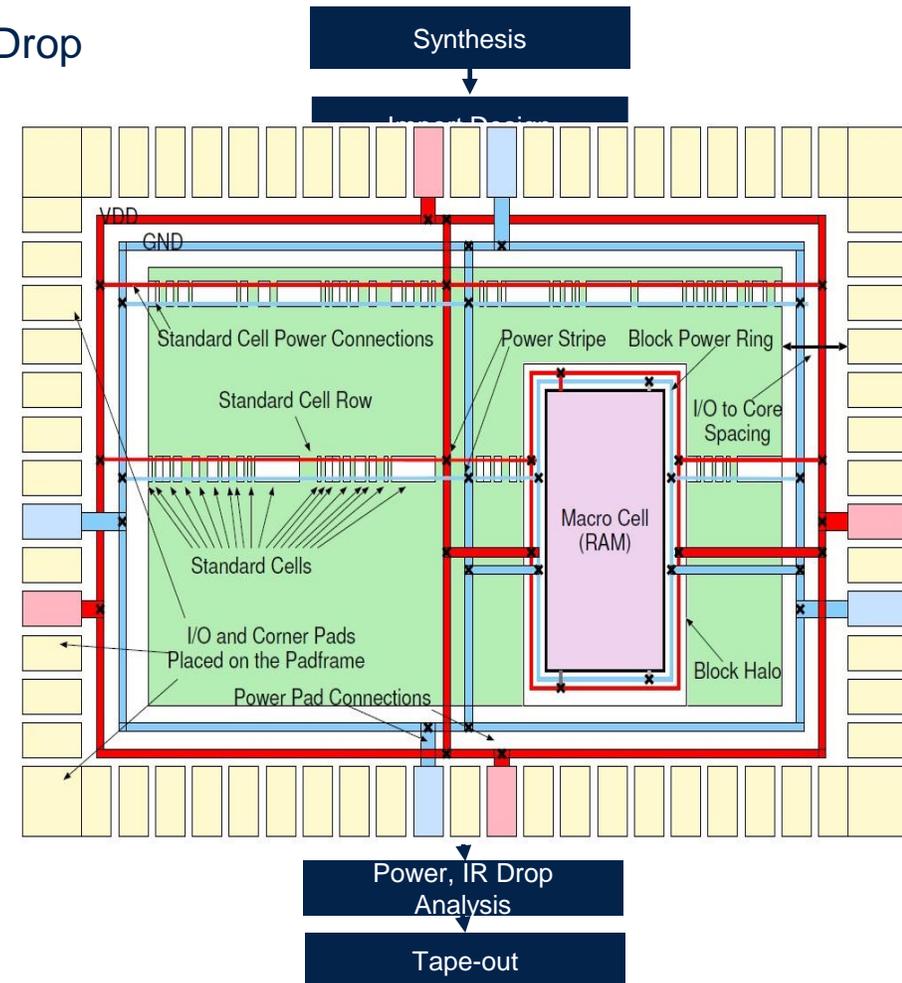
- ❑ Connect  $V_{DD}$  &  $V_{SS}$  to the std cells

- ❑ Power Vias

- ❑ Insert Vias between ring/grid, and horizontal and vertical grid

- ❑ Trunks

- ❑ Connects ring to Power Pad
- ❑ Trunk is a piece of metal that connects IO Pad and Core Ring



# Pre-Placement

## ❑ Physical Only Cells (Well Taps, End Caps)

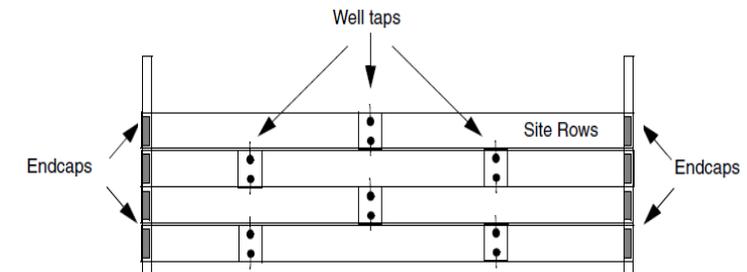
- ❑ These cells do not have signal connectivity and connect only to the power and ground rails
- ❑ End Caps ensure that gaps do not occur between the Well and Implant Layers and prevents DRC violations
- ❑ Well Taps help to tie Substrate and N-wells to VDD and VSS levels and thus prevent Latch-up

## ❑ Special Cells (Spare cells, Decap Cells)

- ❑ Spare Cells for ECO and Decaps for avoiding Instantaneous Voltage Drop (IVD)

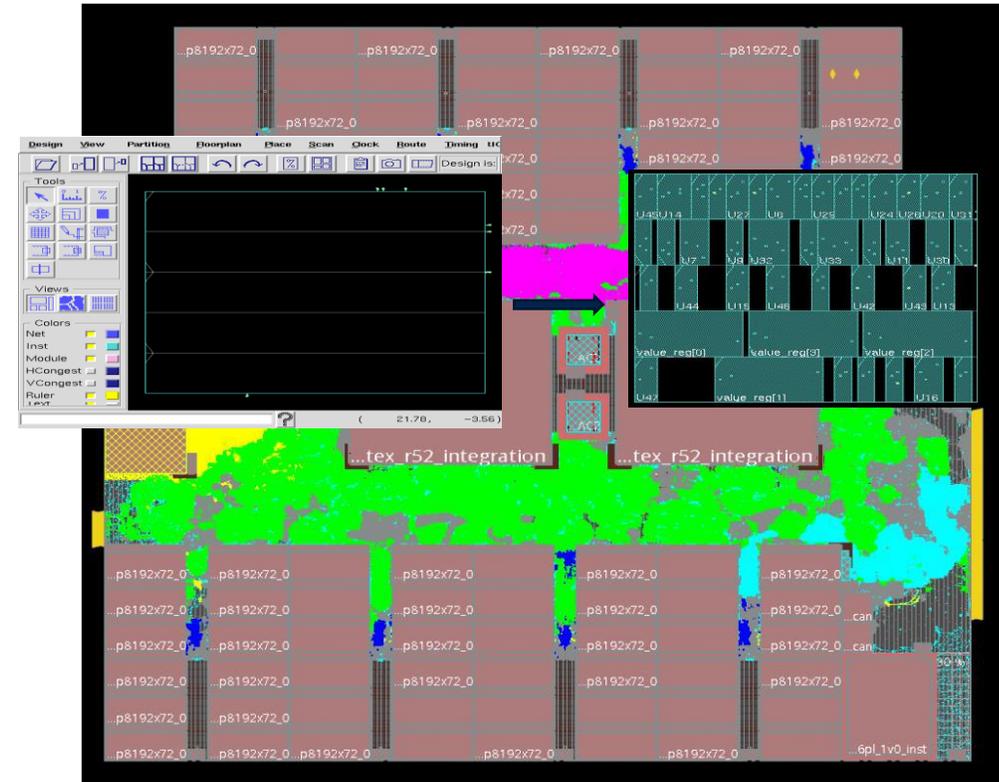
## ❑ Cell Padding

- ❑ Cell Padding is done to reserve space for avoiding Routing Congestion
- ❑ Cell Padding adds Hard Constraints to Placement
- ❑ The Constraints are honored by Cell, Legalization, CTS, and Timing Optimization.



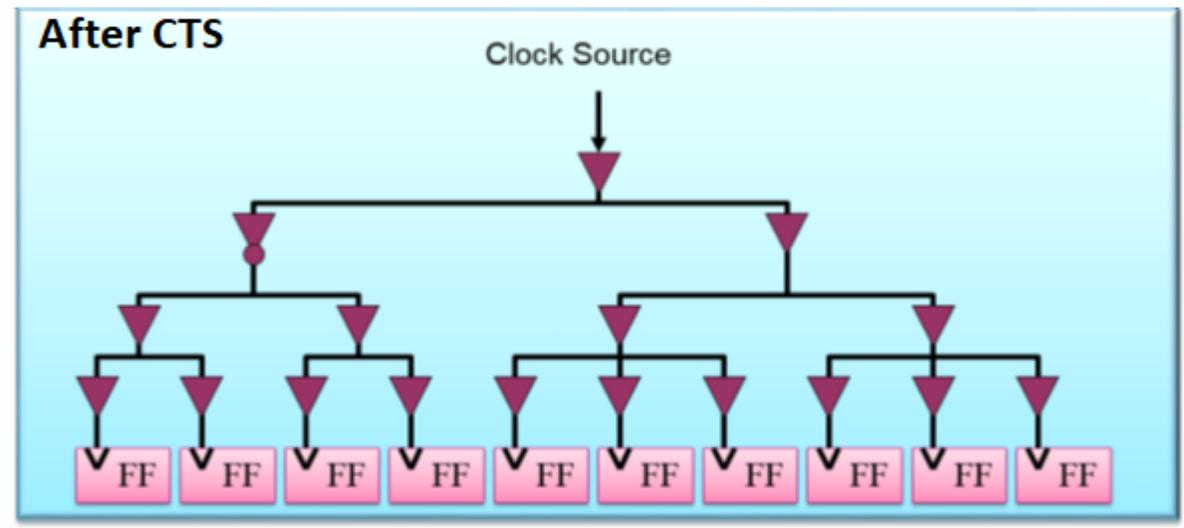
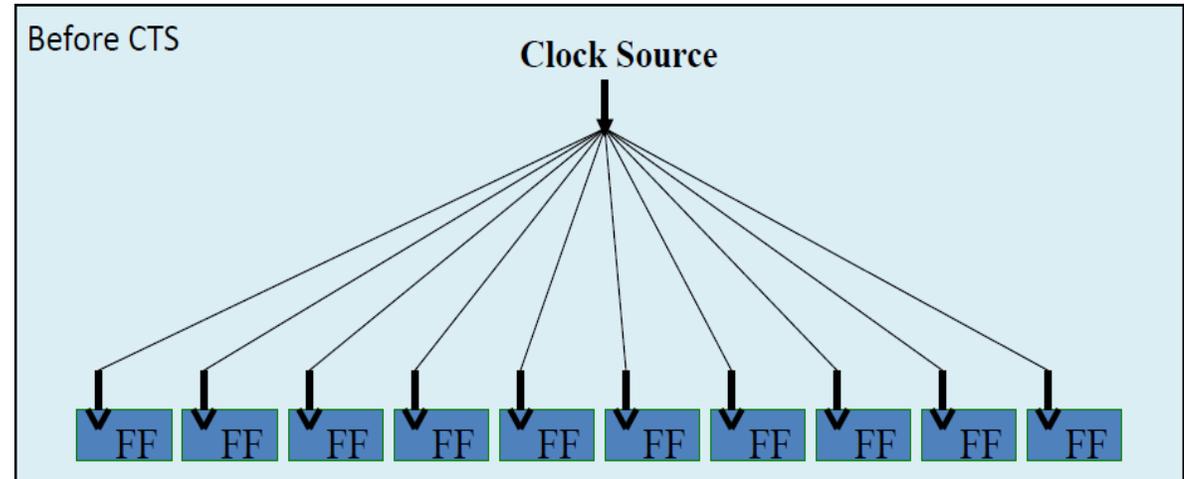
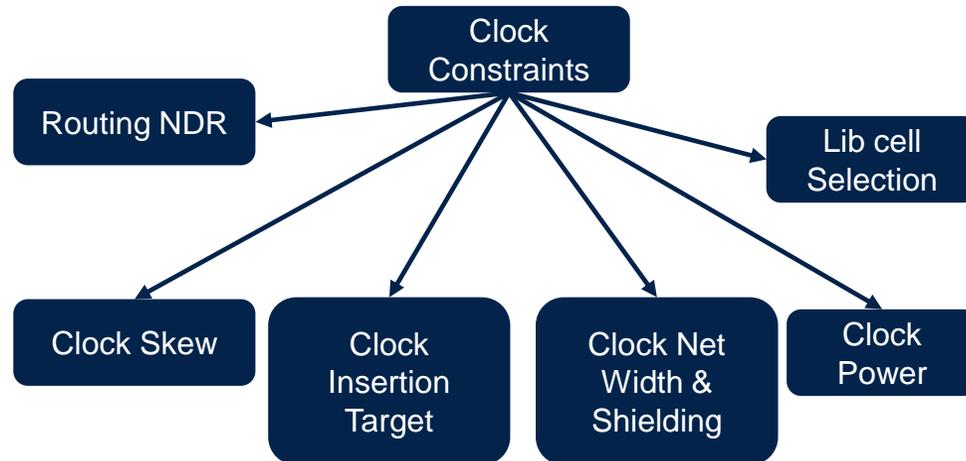
# Placement

- ❑ Automated std cell placement on placement tracks.
- ❑ Placement Objectives
  - ❑ Total wire length
  - ❑ Routability
  - ❑ Performance
  - ❑ Power
  - ❑ Heat distribution
- ❑ Timing checks at Placement stage
  - ❑ Only Setup Time check, since clock is ideal at placement stage
- ❑ Placement Methods
  - ❑ Timing Driven Placement
  - ❑ Congestion Driven Placement



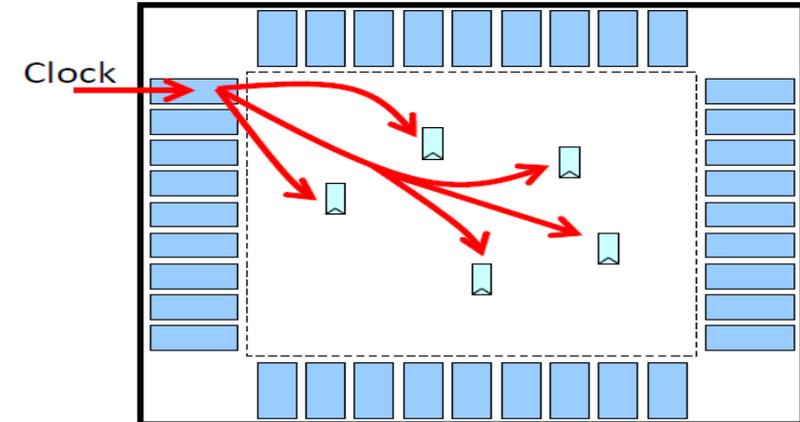
# Clock Tree Synthesis (1/3)

- ❑ What is clocks Tree ?
- ❑ Clock Spec file from SDC
  - ❑ Definition of Clocks
  - ❑ Clock Balance Constraints
  - ❑ Stop & Ignore pins
  - ❑ Macro pin insertion delay
  - ❑ Exclusive Sink Groups
  - ❑ Early Clock for Dividers

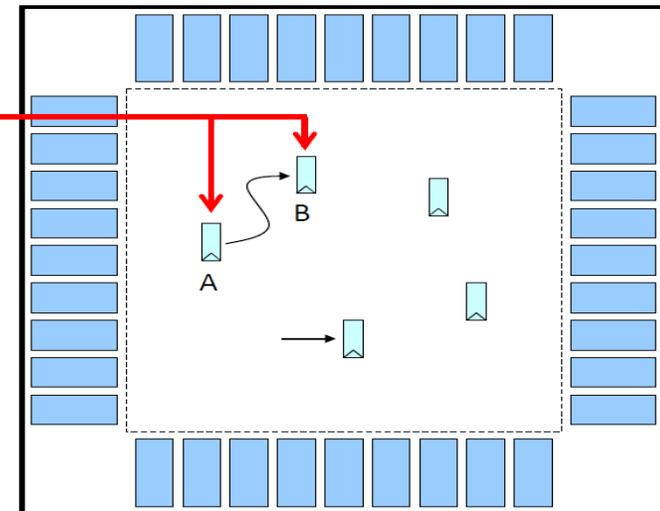


# Clock Tree Synthesis (2/3)

- ❑ Skew: Most important concern for Clock Networks.
  - ❑ Due to variations in trace length, metal width and height, coupling caps.
  - ❑ Also due to variations in local clock load, local power supply, local gate length and threshold, local temperature.
- ❑ Power: Major power consumer.
  - ❑ Clock cell switches at every clock cycle.
- ❑ Noise:
  - ❑ Clock is often very strong aggressor
  - ❑ May need shielding
- ❑ Delay:
  - ❑ Clock Insertion Delay is important
  - ❑ Good transition on clock network.

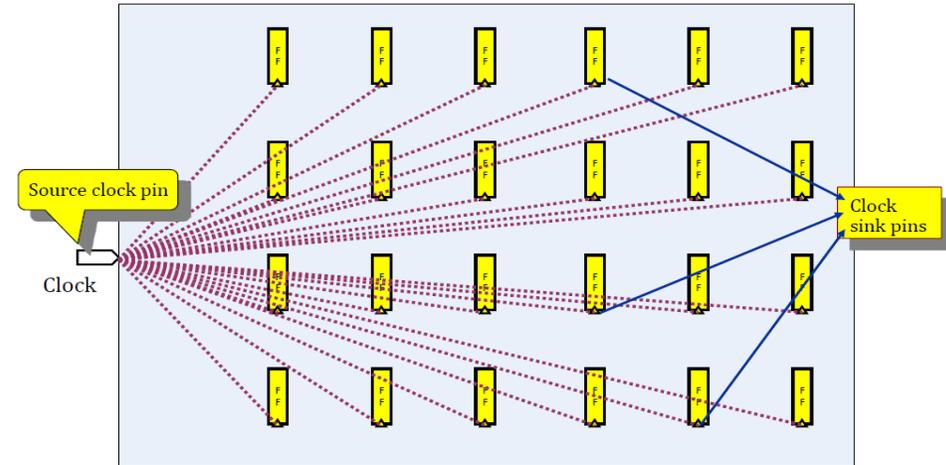


**Clock Skew**  
Difference in clock arrival time at two spatially distinct points

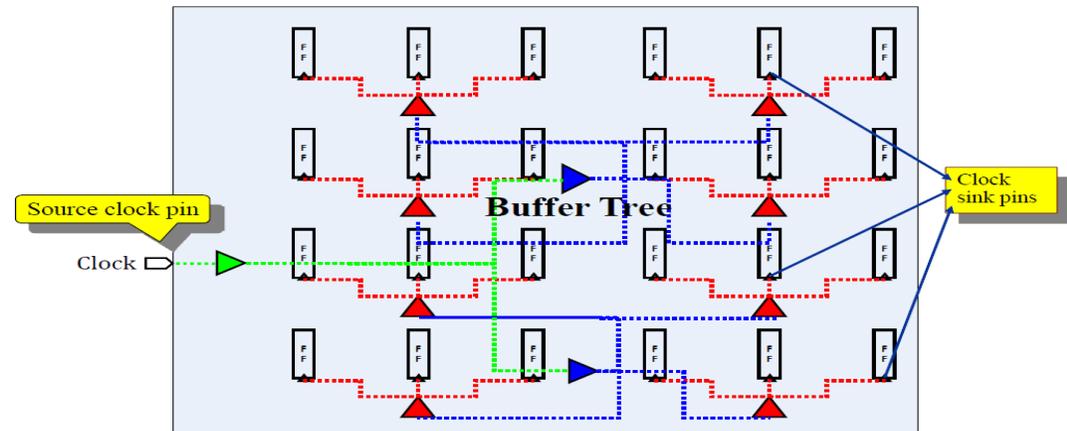


# Clock Tree Synthesis (3/3)

- ❑ Before CTS, all Clock Pins are driven by a single Clock Source.

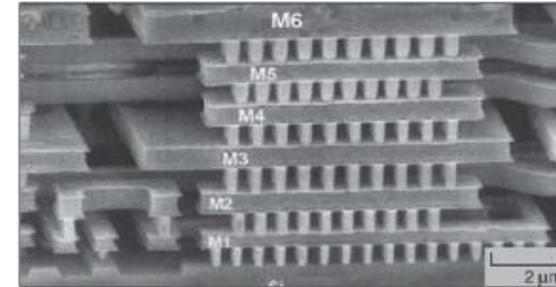


- ❑ After CTS, the buffer tree is built to balance the loads and minimize the skew.

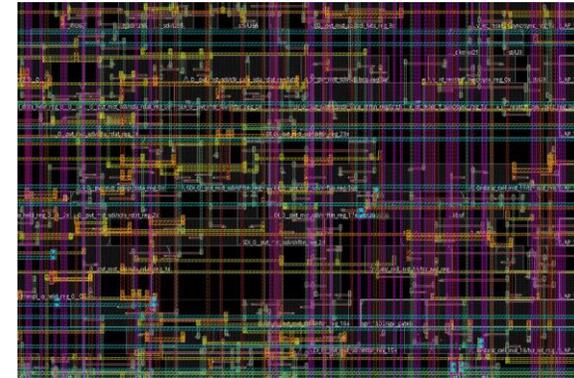


# Routing (1/3)

- ❑ Routing Objectives : Connections are routed as connected logically
- ❑ Routed paths must meet setup & hold timing margin.
- ❑ DRVs max. Capacitance/ Transition must be under the limit.
- ❑ Metal traces must meet foundry physical DRC requirements.
- ❑ Layout geometries should meet Current Density specification.



**Multi-level Interconnection (MLI)  
Technology Layer stacks**



# Routing (2/3)

## ❑ Trial/Global Routing:

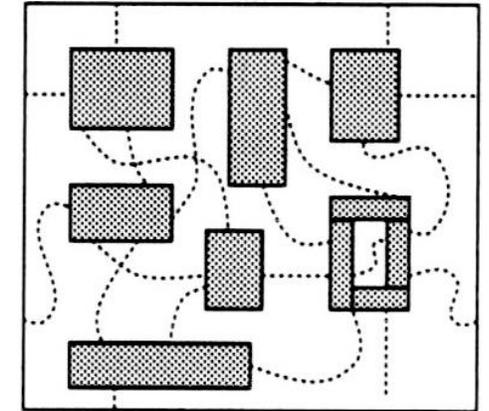
- ❑ Routable path for the nets driving/ driven pins in a shortest distance.
- ❑ Does not consider DRC rules, which gives an overall view of routing and congested nets
- ❑ Assign net to specific routable window, i.e Global Route Cell (GRC)
- ❑ Avoid congested areas and also long detours and avoid routing over blockages
- ❑ Avoid routing for pre-route nets such as Rings/Stripes/Rails
- ❑ Uses Steiner Tree and Maze algorithm

## ❑ Track Assignment:

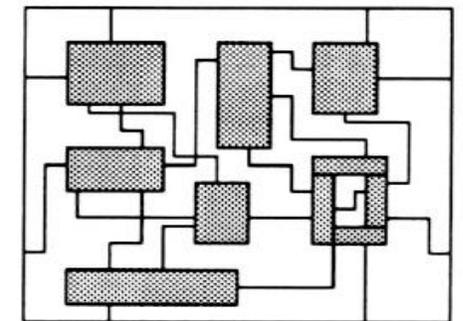
- ❑ Takes the Global Routed Layout and assigns each nets to the specific Tracks and layer geometry
- ❑ It does not follow the physical DRC rules but will do the timing aware Track Assignment.

## ❑ Detail/Nano Routing:

- ❑ It follows up with the track routed net segments.
- ❑ It Performs complete DRC aware and timing driven routing
- ❑ Final routing for the design built after the CTS and the timing is freeze.



Global Routing



Detailed Routing

# Routing (3/3)

## ❑ Grid Based Routing:

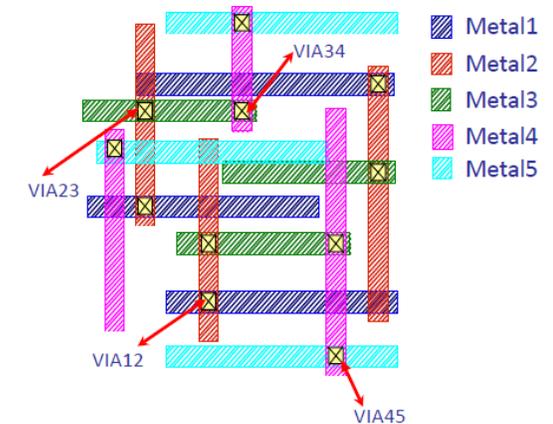
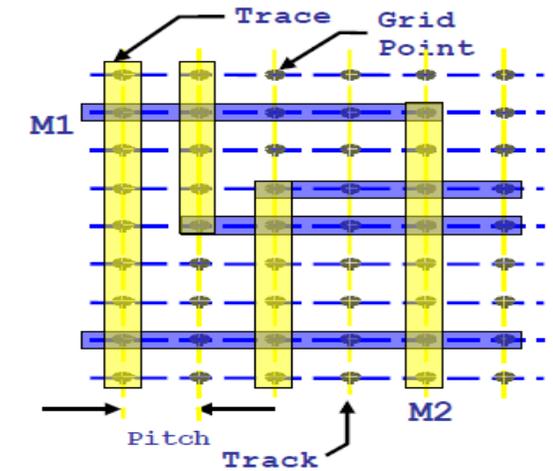
- ❑ Metal traces (routes) are built along and centered upon routing tracks.
- ❑ Various types of grids are Manufacturing Grid, Routing Grid (Pitch) and Placement Grid.
- ❑ Grid dimension should be multiple of Manufacturing Grid.

## ❑ Routing Preferences:

- ❑ Typically Routing only in “Manhattan” N/S E/W directions.
- ❑ Spacing checks with the adjacent layers.
- ❑ Width check for all layers and via dimension rules.

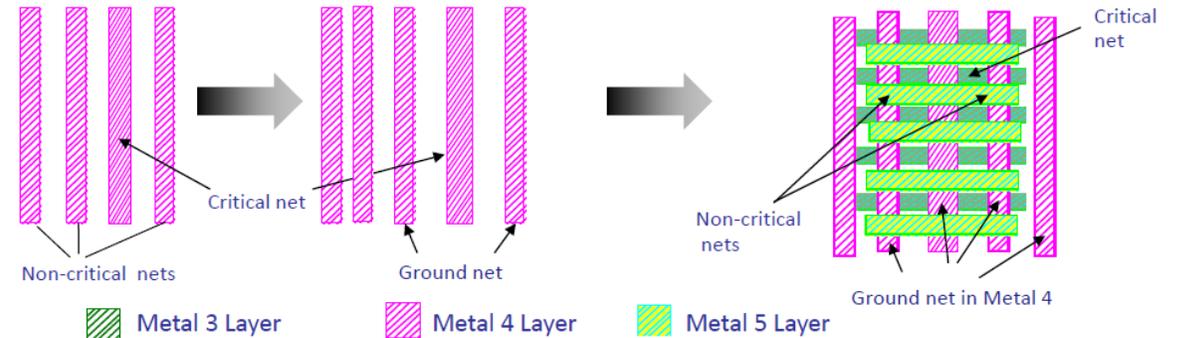
## ❑ Layer Routing directions:

- ❑ Each metal layer has its own preferred routing direction and are defined in a technology rule file.
- ❑ M1: Horizontal, M2: Vertical , M3: Horizontal, M4: Vertical and so on...
- ❑ In some cases, we can avoid following preferred routing direction for smart routing (Non-preferred direction)

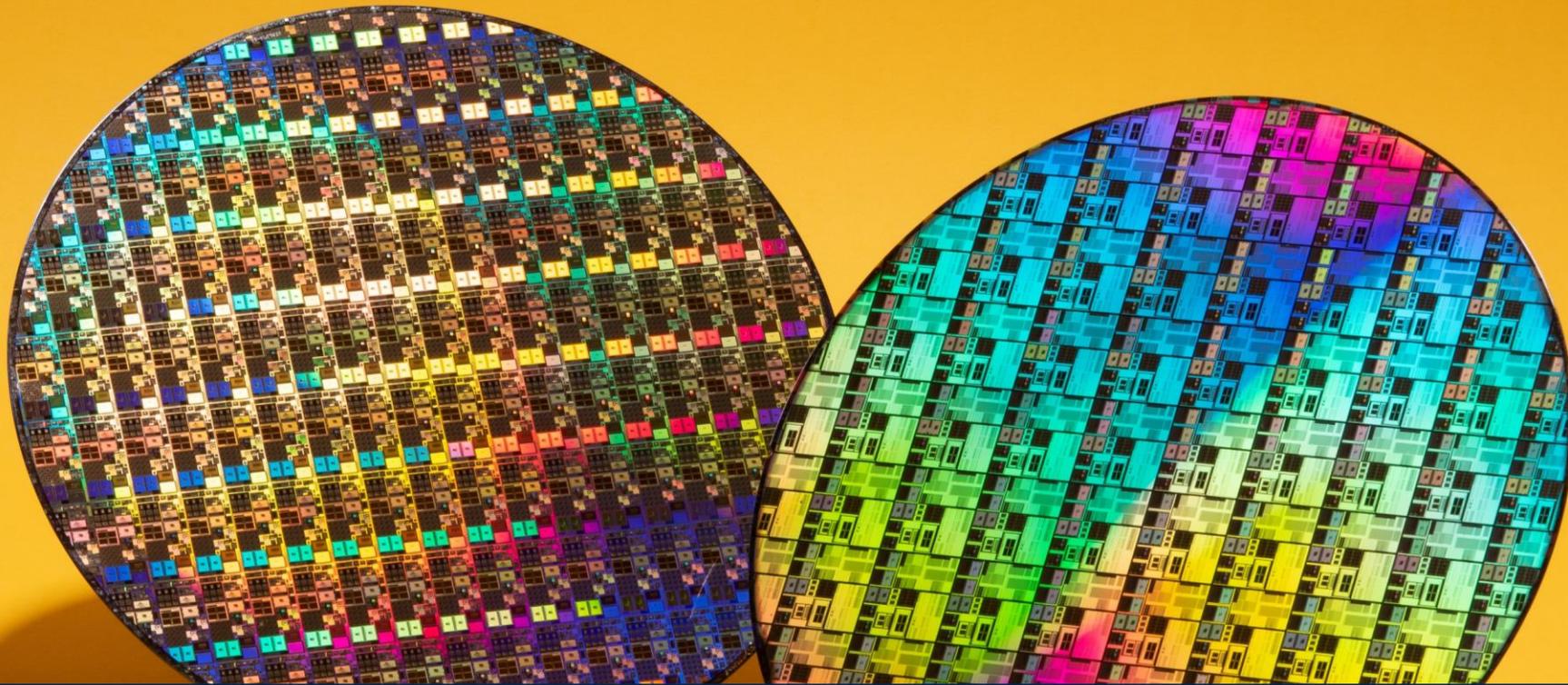


# Post Routing Optimization

- ❑ Signal Integrity (SI) Optimization by NDRs and Shielding for the sensitive nets
- ❑ Types of Shielding for sensitive nets
  - ❑ Same layer shielding
  - ❑ Adjacent layer/ Coaxial shielding
- ❑ Metal Fill: Filling up empty metal tracks.
  - ❑ Floating Metal Fills
  - ❑ Grounded Metal Fills



# Signoff



## Physical Verification: DRC and LVS

- DRC: Fabrication related rules : Spacing and Notch etc
- LVS: layout versus schematic : GDSII versus CDL.

## Timing Signoff

- Design meets frequency specs
- No setup – hold violations
- All DRVs met (max-capacitance, max-transition, fan-out)

## Power Signoff

- Static: IR Drop Analysis
- Dynamic: IR Drop Analysis

# Physical Verification (DRC)

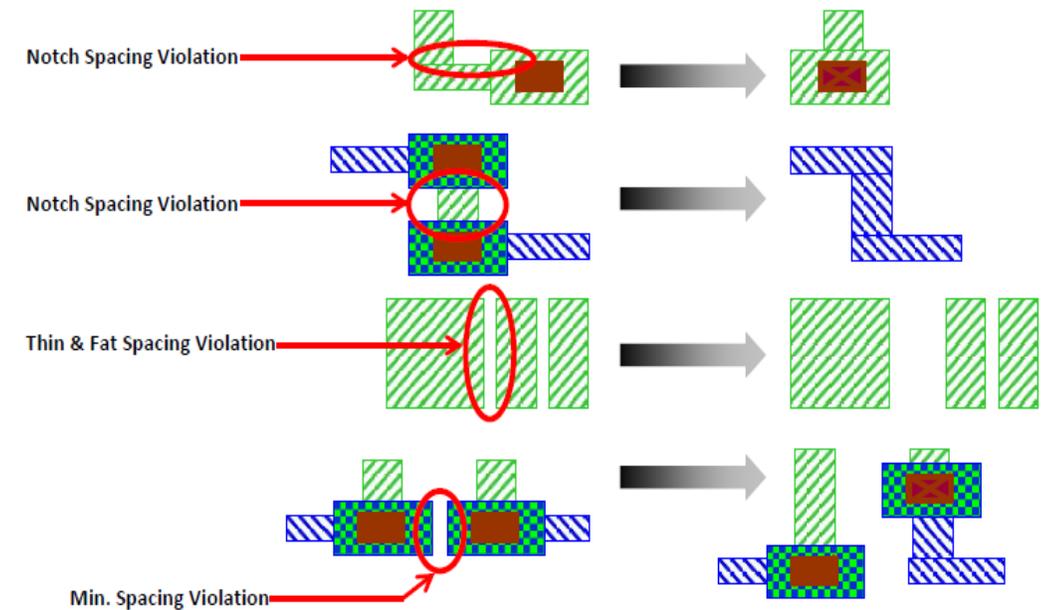
- Design Rule Check (DRC) is the process of checking physical layout data against fabrication-specific rules specified by the foundry to ensure successful fabrication.
- Process specific design rules must be followed by drawing layouts to avoid any manufacturing defects during the fabrication of an IC.
- As Technology Shrinks
  - Number of Design Rules are increasing
  - Complexity of Routing Rules is increasing
  - Increasing the number of objects involved
  - More Design Rules depending on Width, Halo, Parallel Length
- Violating a design rule might result in a non-functional circuit or low Yield.



# Physical Verification (DRC)

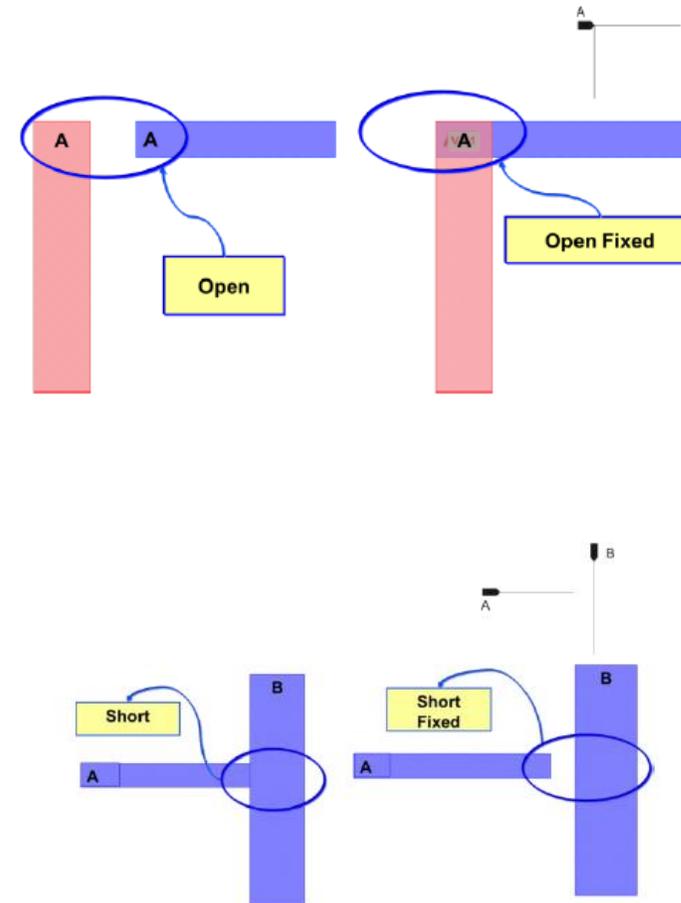
## ❑ Design Rule examples:

- ❑ Maximum Rules: Manufacturing of large continuous regions can lead to stress cracks. So 'wide metal' must be 'slotted' (holes)
- ❑ Grid: All corner points must lie on a minimal grid, otherwise an "off grid error" is produced
- ❑ Minimum Spacing: The minimum spacing between objects on a single layer
- ❑ Minimum Width: The min width rule specifies the minimum width of individual shapes on a single layer
- ❑ Minimum Enclosure/ Overlap: Implies that the second layer is fully enclosed by the first one
- ❑ Notch: The rule specifies the minimum spacing rule for objects on the same net, including defining the minimum notch on a single-layer, merged object
- ❑ Minimum Cut: the minimum number of cuts a via must have when it is on a wide wire



# Physical Verification (LVS)

- Layout Versus Schematic (LVS) verifies the connectivity of a Verilog Netlist and Layout Netlist (Extracted Netlist from GDS)
- Tool extracts circuit devices and interconnects from the layout and saved as Layout Netlist (SPICE format)
- As LVS performs comparison between 2 Netlist, it does not compare the functionalities of both the Netlist
- Input Requirements
  - LVS Rule deck
  - Verilog Netlist
  - Physical layout database (GDS)
  - Spice Netlist (Extracted by the tool from GDS)
- LVS checks examples
  - Short Net Error, Open Net Error, Extract errors, Compare errors

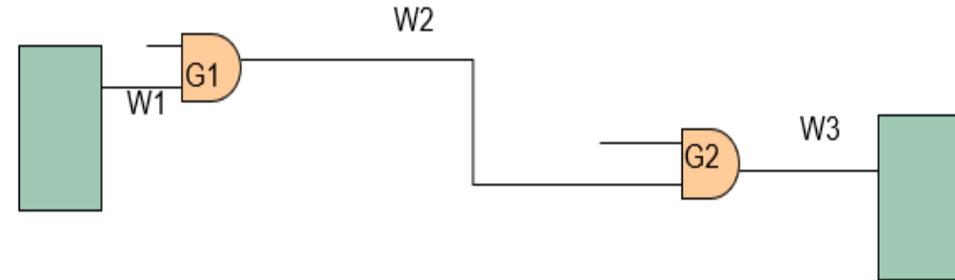


# Timing Signoff

- ❑ To check if the design meets timing constraints in all situations.
- ❑ Static Timing Analysis : Computes both minimum and well as maximum range of delay values of all possible combination of inputs
- ❑ First stage STA done at gate level netlist.
- ❑ Where does timing come from ?
  - ❑ Gates: PVT (operating conditions)
  - ❑ Connections: (load Cap, and input tran).
  - ❑ Wire: parasitic (resistance, Capacitance)

## ❑ STA: Principle...

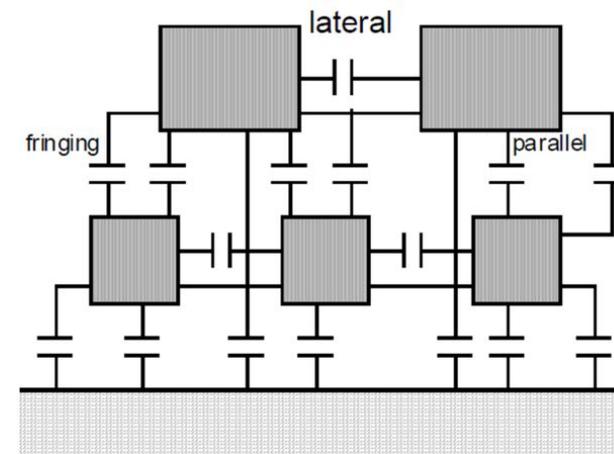
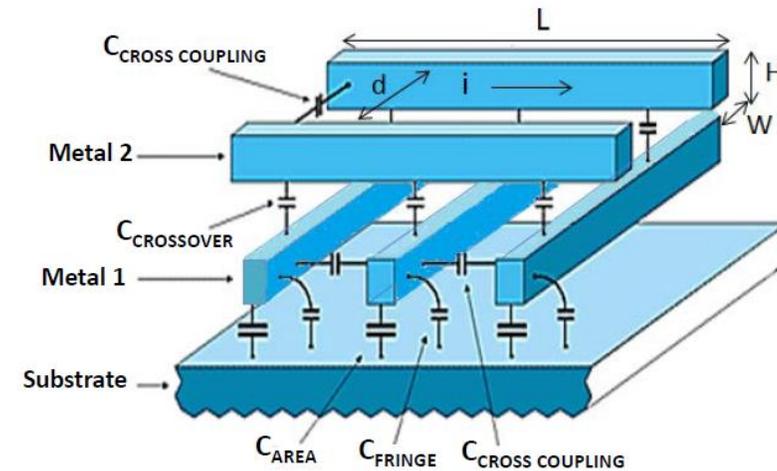
- ❑ To time any and every single gate & wire
- ❑ Sum up these delays on any timing path
- ❑ Check versus the constraints if timing is met



Delay in Gates (G1, G2) + Delay in wires (W1, W2, W3) < Expected delay on the path

# Parasitic Extraction

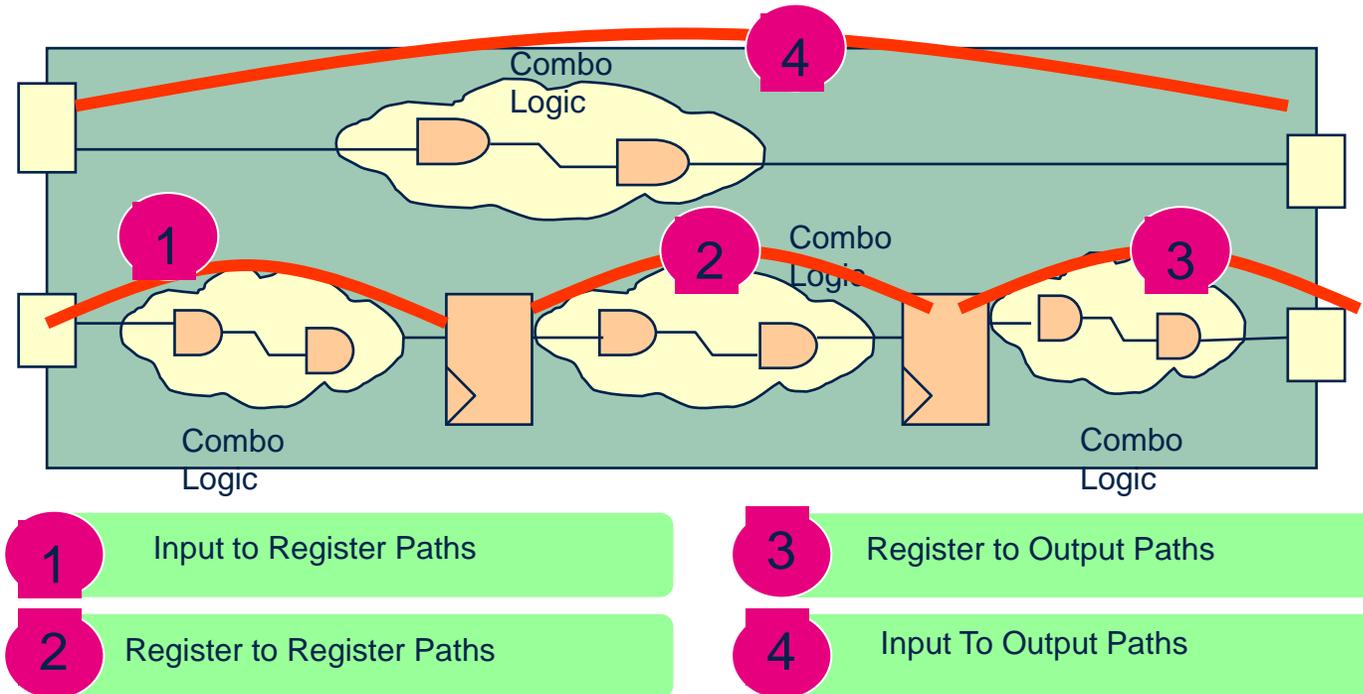
- Capacitance :  $C = \epsilon_0 * W * H / d$ 
  - Transistors: Depends on area of transistor gate, physical of materials, thickness of insulator, diffusion to substrate
  - Poly to Substrate: Parallel plate and fringing.
- Capacitance between conductors: Coupling cap, Area cap, Fringing cap and Crossover cap.
- Coupling Cap / Lateral Cap
- Fringing Cap
- Parallel/Crossover Cap
- Area Cap



# Static Timing Analysis

## ❑ Default #4 types of timing paths:

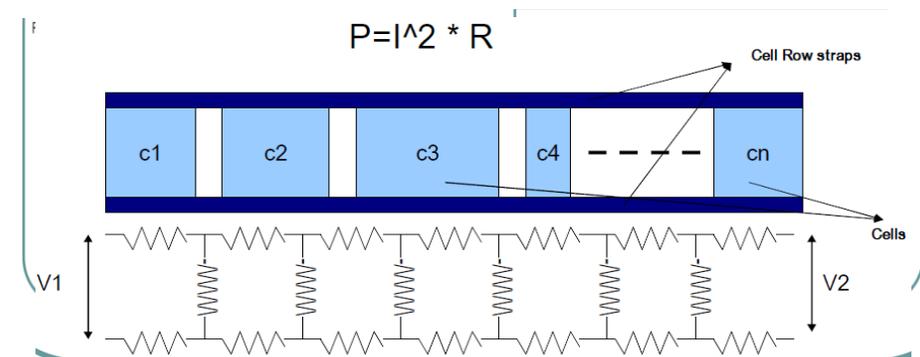
- ❑ In2Reg
  - ❑ Reg2Out
  - ❑ Reg2Reg
  - ❑ In2Out
- ❑ Setup and Hold check
  - ❑ Max Transition and Max Capacitance check



# IR Drop Analysis

- Why worry about IR drop analysis ?
  - Poor-floor planning
  - Problems in power routing such as: Unconnected contact arrays, Power grid discontinuities.
  - Insufficient power pins
  - Incorrect power-pin placement
  - Faster clocks => higher power consumption, need to offset by scaling C and Vdd
  - Shrinking wire cross-sections => higher wire and via resistances values
- Power dissipation on the silicon will happen because of following reasons.
  - Static components
  - Dynamic components
  - Power distributions

- Static Components
  - Subthreshold Leakage
  - Tunneling Current
  - Reverse Biased diode leakage
- Dynamic Components
  - Switching and Short circuit analysis
  - Charging and discharging of the load capacitances.
  - Short circuit current through PMOS and NMOS transistors when they are partially on.
- Power Distribution : Ohm's law applicable

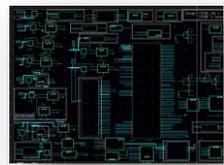


# Tape-out

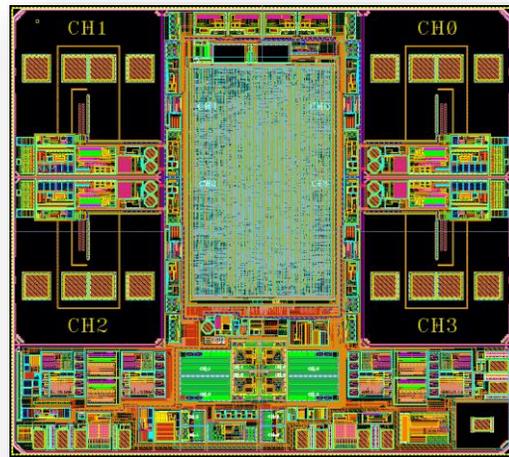


# Tape-out

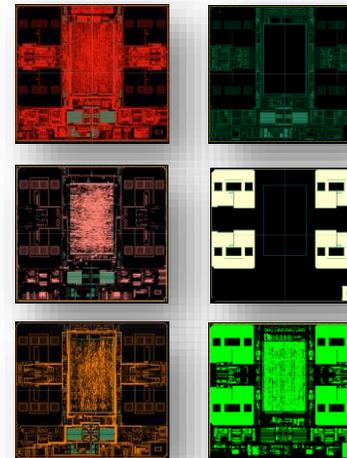
- Chip is ready to be manufactured 😊



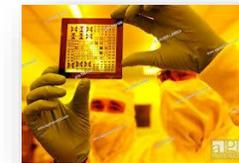
**SCHEMATIC**



**LAYOUT**



**MASK LAYERS**

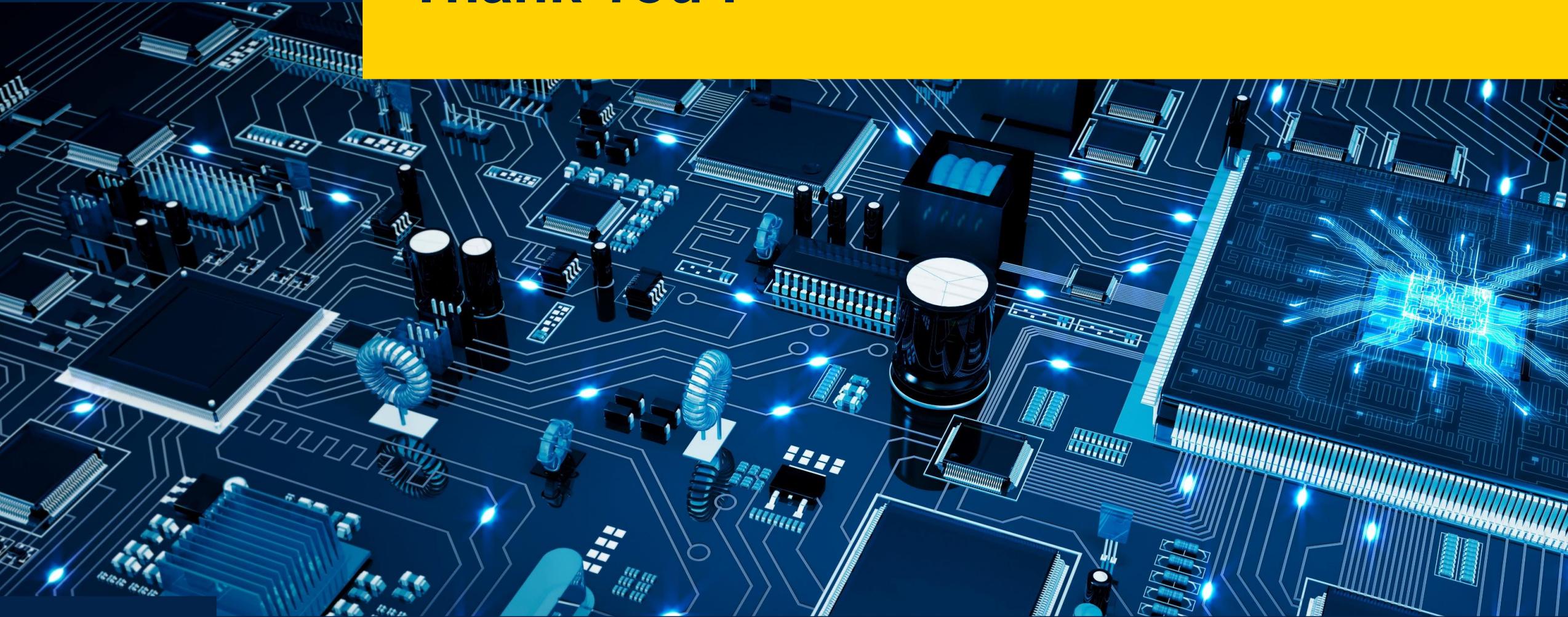


**PHOTOLITHOGRAPHY  
MASK**



**CHIP ON WAFER**

**Thank You !**



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